

# Use of Nanotechnology for Electronics Packaging Applications – European View

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- **Funded EU Programs in 7th Frame Program in ICT fields with focus on Nanoelectronics**
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- **Reliability models development**
- **Encapsulaton of OLED devices with Nano-ACA**

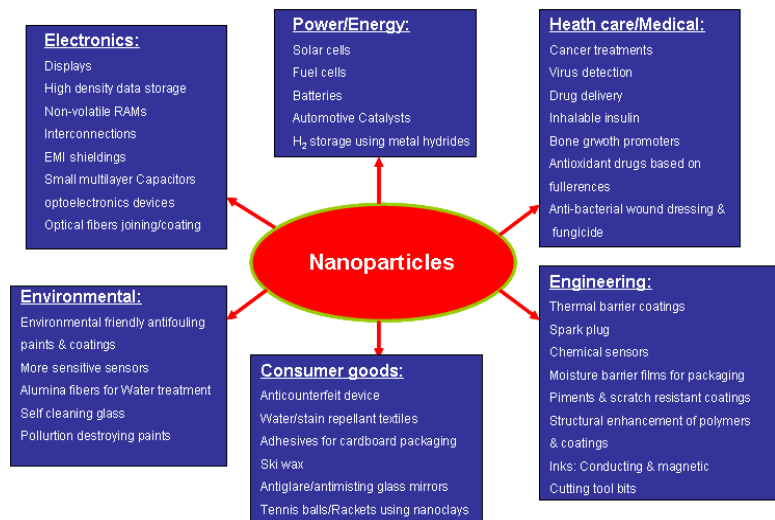


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## Definition of Nano Particles

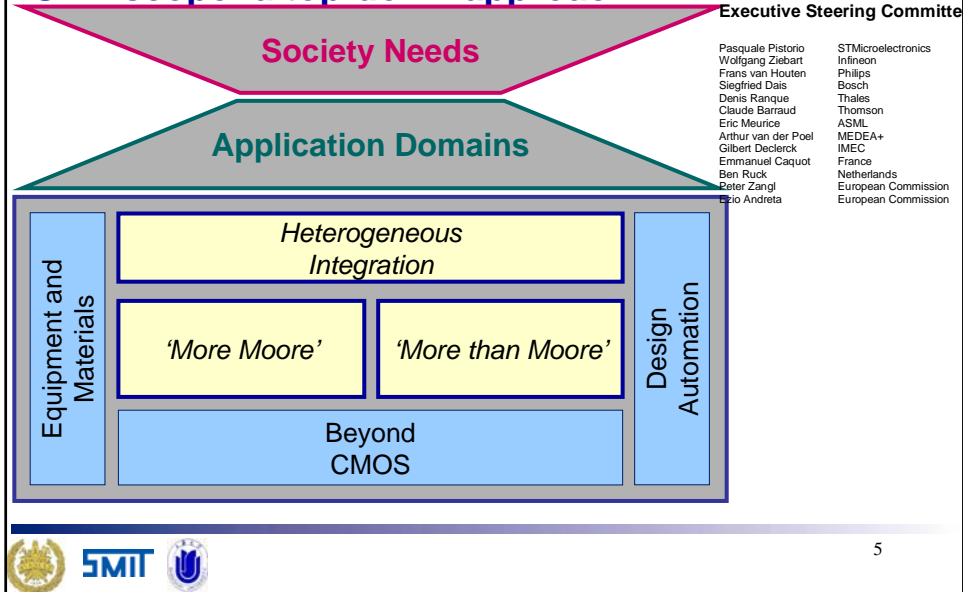
Particles in size range  $10^{-9}$ m are known as nanoparticles or sub-micron particles. They are also known as quantum dots due to quantum property possessed by them.

## Nanoparticles in Various Fields

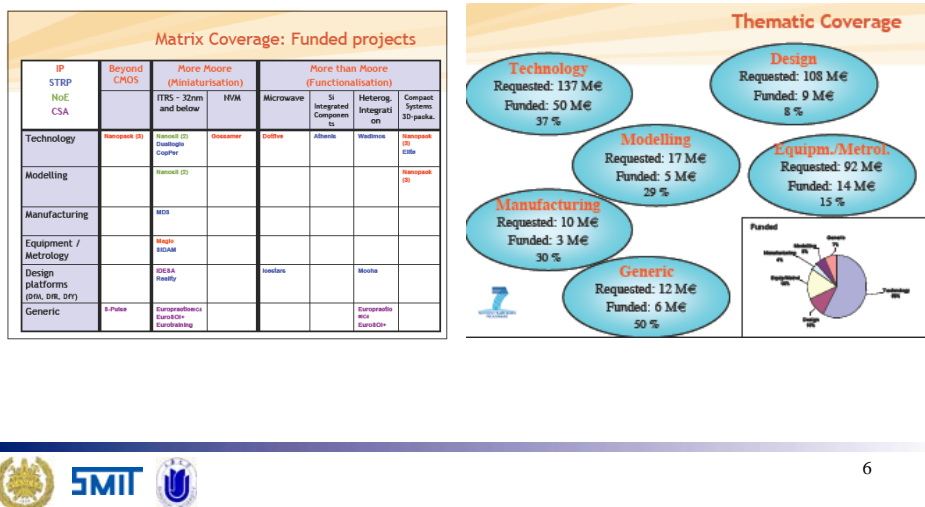


# European Network for Nanoelectronics (ENIAC)

## SRA scope: a top-down approach



## IST-2007.3.1: Next-Generation Nanoelectronics: Components and Electronics Integration - Funding results (Ref: Vergera, EU)



# IST-2007.3.1: Next-Generation Nanoelectronics: Components and Electronics Integration; EU IP Project

Large-scale integrating project (IP) proposal

ICT Call 1

FP7-ICT-2007-1

Proposal No: 216176

Total budget 12 MEURO

## Nano Packaging Technology for Interconnect and Heat Dissipation

### NANOPACK

Participant no. *	Participant organisation name	Part. short name	Country
1 (Coordinator)	Thales Research & Technology	TRT	France
2	Budapest University of Technology and Economics	BME	Hungary
3	Robert Bosch GmbH	Bosch	Germany
4	Institut d'Electronique de Microtechnologie et de Nanotechnologie (CNRS in A2 form)	IEMN	France
5	Chalmers University of Technology	CHALMERS	Sweden
6	Electrovac AG	EVAC	Austria
7	FOAB Elektronik AB	FOAB	Sweden
8	Fraunhofer Institute IZM	F-IZM	Germany
9	IBM Zürich Research Laboratory	IBM	Switzerland
10	Catalan Institute of Nanotechnology	ICN	Spain
11	MicReD Ltd.	MicReD	Hungary
12	Berliner Nanotest und Design GmbH	Nanotest	Germany
13	Thales Avionics	THAV	France
14	VTT Micro- and Nano-electronics	VTT	Finland

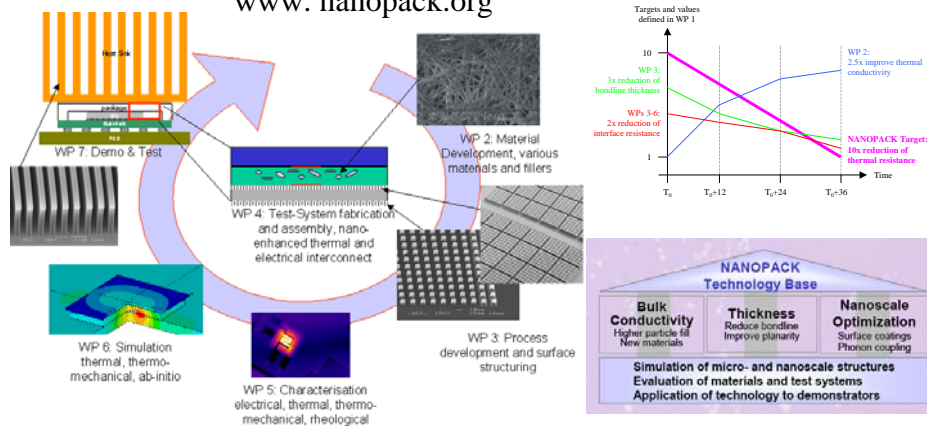


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## Overall objective of the NANOPACK Program

Develop new thermal interface technologies for low thermal resistance by employing nano-modified surfaces and materials along with methods for characterization and simulation with respect to thermal, electrical and reliability-related properties.

[www.nanopack.org](http://www.nanopack.org)



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Nano-Pack Focus at SMIT Center,  
Chalmers University of Technology

Nano-Thermal interface material

package  
Die  
Substrate  
FCB

CNT-based high thermally  
conductive fine pitch interconnects

CNT-based microchannel coolers

SMIT

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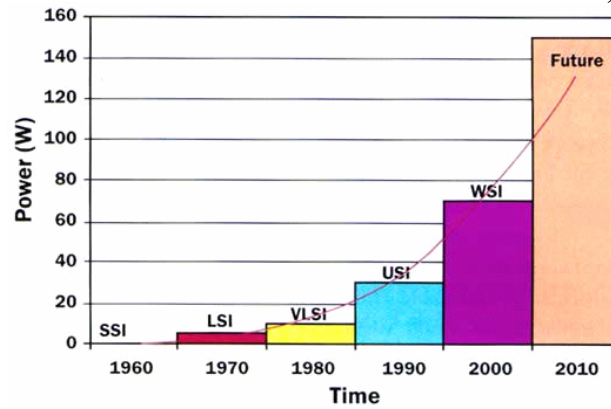
## Nano-Thermal Interface Material

SMIT

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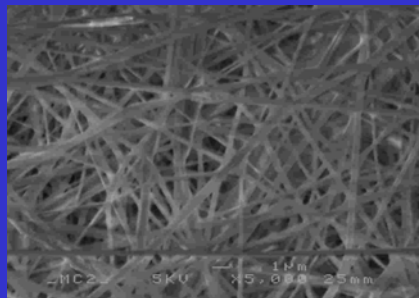
## Heat development of CPU

“If chip makers had continued on their old path, by the year 2015, microprocessors would be throwing off more watts per square millimeter than the surface of the sun.” – *IEEE SPECTRUM, 1st Issue, 2006*



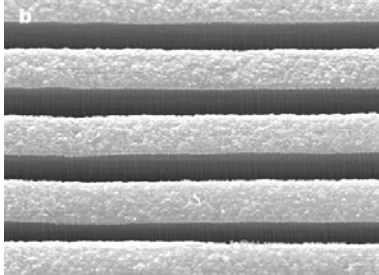
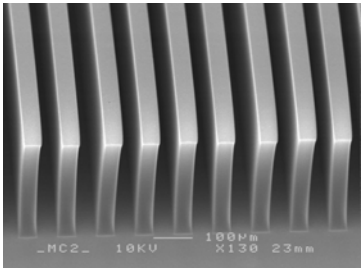
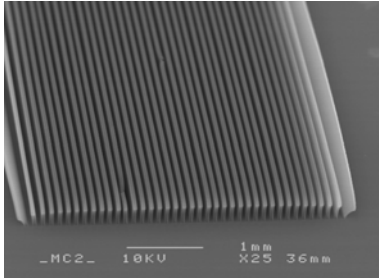
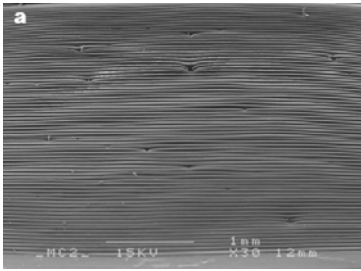
Timeline plot of device technology with respect to power dissipation  
(source: [http://www.electronics-cooling.com/html/2000\\_dec\\_a1.html](http://www.electronics-cooling.com/html/2000_dec_a1.html))

## Nano-TIM



# Microcooler Based CNT

## CNT-based microchannel coolers



## Results

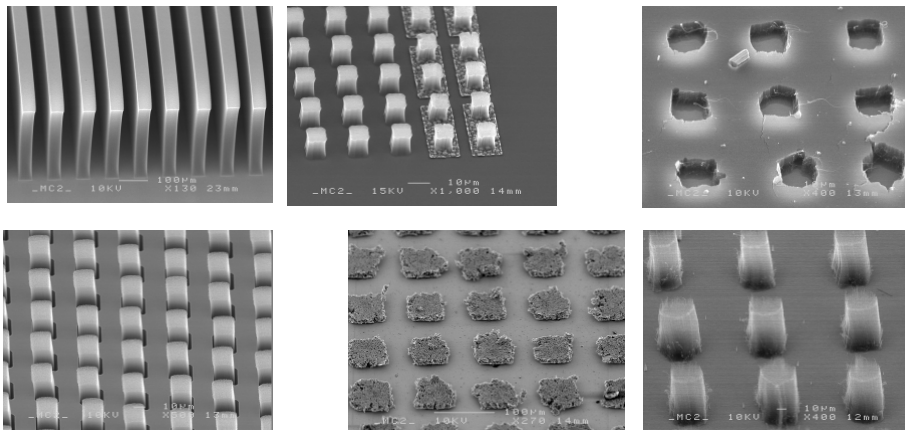
50 $\mu$ m wide channels. Heights of the fins are 100 $\mu$ m and 300 $\mu$ m respectively. The surrounding temperature is 23°C.

Sample	1	2	3	4
Description	CNT cooler	Silicon cooler with fins	Silicon cooler without fins	Natural air convection
Power of resistor (W)	2.13	1.95	1.95	1.85
Flow rate (ml/min)	35.7	38.5	34.5	/
Temperature of resistor (°C)	42	42	50	56

Development and Characterization of Microcoolers using Carbon Nanotubes, Teng Wang, Martin Jönsson, Elisabeth Nyström, Zhimin Mo, Eleanor E.B. Campbell and Johan Liu, ESTC2006, September 5-7, 2006, Dresden, Germany, pp.881-885.



## CNT based packaging research and development at SMIT Center



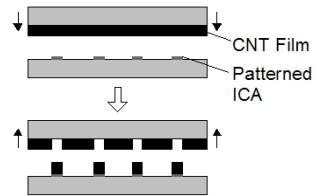
- Growth of CNTs with or without patterns on different substrates
- Low temperature transfer of CNTs by conductive adhesives
- Integration of these technologies into various structures



## Transfer of CNT Bundles

- Motivation

- to integrate CNTs into temperature-sensitive processes and materials (CNT growth temperature normally higher than 700°C)
- to promote the adhesion between CNTs and the substrate



- Technology used

- Transfer of un-patterned CNT film by patterned isotropic conductive adhesive (ICA)



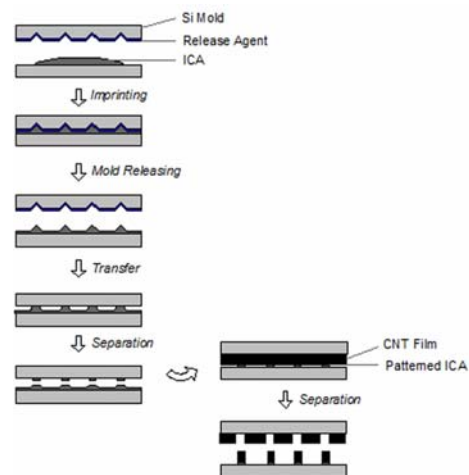
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## CNT Transfer by ICA

- Patterning of ICA

- An “imprinting and transfer” process

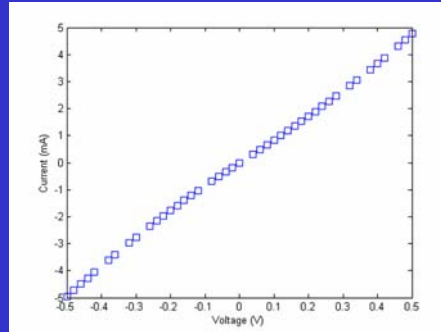
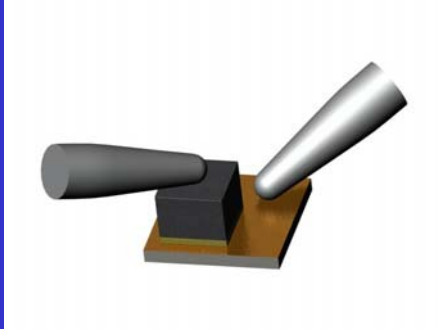
- The transfer and formation of CNT bumps achieved at the same time



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## IV Measurement of CNT-ICA Structure

- Two probe measurement

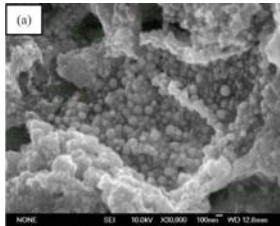


Low Temperature Transfer and Formation of Carbon Nanotube Arrays by Imprinted Conductive Adhesive, T. Wang, B. Carlberg, M. Jönsson, G.-H. Jeong, E. E.B. Campbell and J. Liu, APPLIED PHYSICS LETTERS **91**, 093123 \_2007.

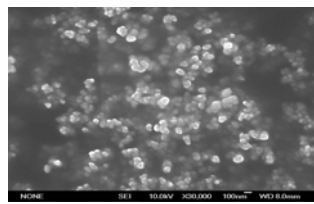


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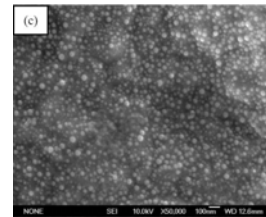
## Nano Lead Free Solder Paste



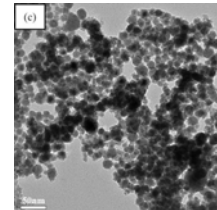
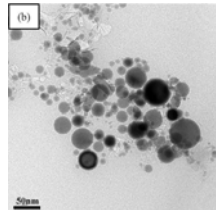
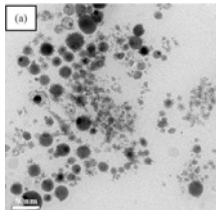
(a) Sn-3.0Ag-0.5Cu,



(b) Sn-0.4Co-0.7Cu



(c) Sn-57Bi

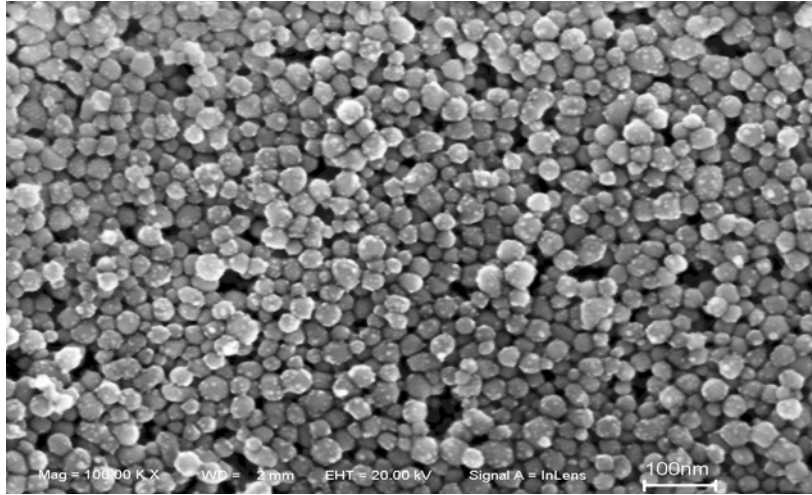


Characterization of Nanoparticles of Lead Free Solder Alloys, Wanbing Guan, Suresh Chand Verma, Yulai Gao, Cristina Andersson, Qijie Zhai and Johan Liu, (ESTC2006), September 5-7, 2006, Dresden, Germany, pp.7-12.



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## Nanosized-Lead Free Powder: Sn58Bi

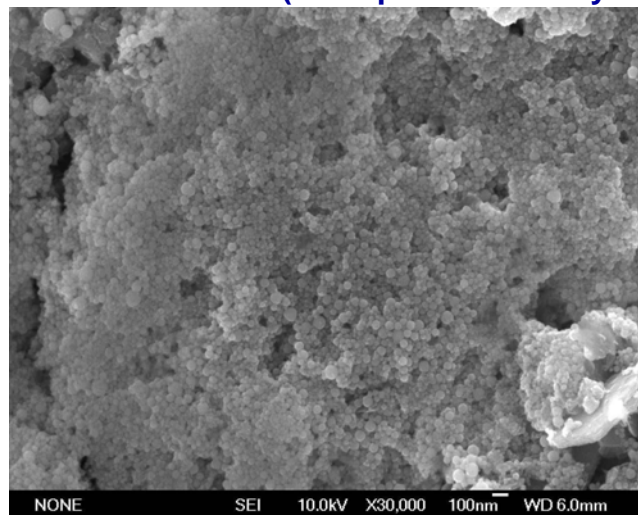


TMS Online Spotlight paper, Sept 5, 2007 <http://materialstechnology.tms.org>



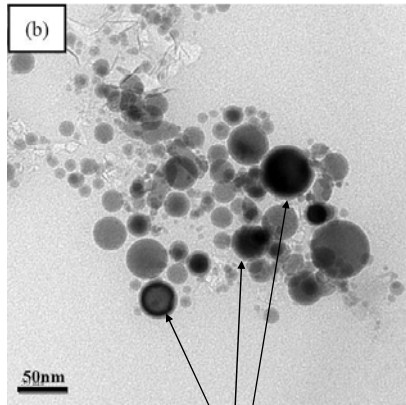
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## High volume of nanoparticles produced with good size control and distribution (Example: SAC305 system)

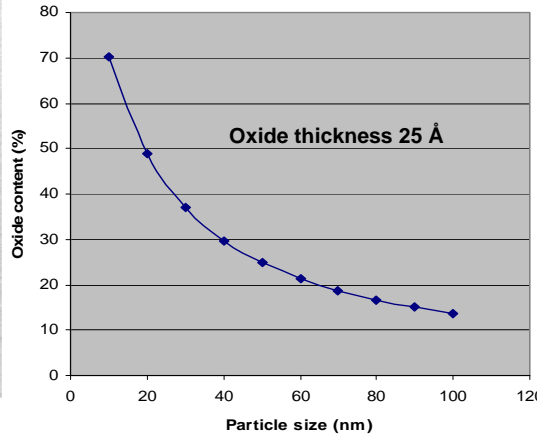


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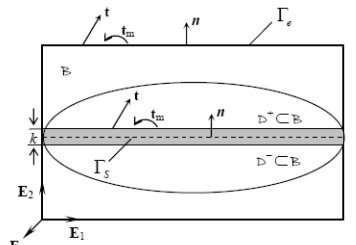
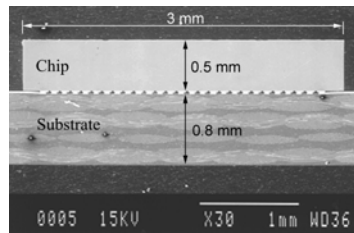
# Oxide content in nano-particles



Sn-0.4Co-0.7Cu nano-particles



## Reliability modelling using micropolar interface model to describe the interfacial properties and inhomogenities for microsystems



Sketch map of the interconnect system

Displacement  $\mathbf{u} = \mathbf{u}(\mathbf{x}, t)$   
 Rotation  $\theta = \theta(\mathbf{x}, t)$

Interface

$$\mathbf{u} = \mathbf{u}_c(\mathbf{x}, t) + H_s(\mathbf{x})\mathbf{d}_u(\mathbf{x}, t)$$

$$\theta = \theta_c(\mathbf{x}, t) + H_s(\mathbf{x})d_\theta(\mathbf{x}, t)$$

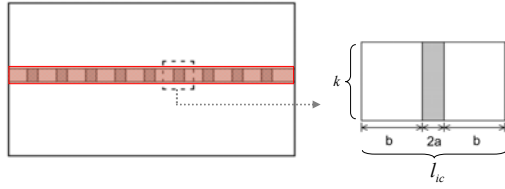
Continuous part      Discontinuity

Regularization

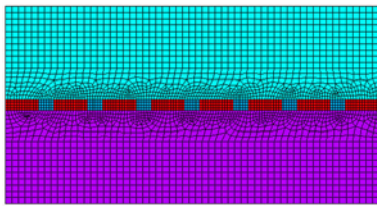
Kinematic equations  
 Balance relations  
 Constitutive relations  
 .....

Micropolar Interface Model

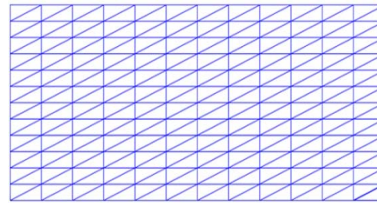
## Interface/interconnect with internal structures



Internal structure parameters can be involved in interface stiffness coefficients (intrinsic)

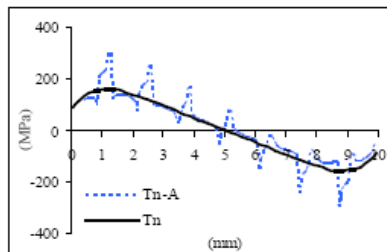
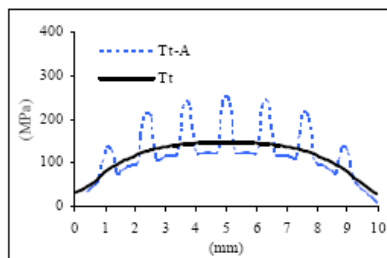


Mesh in ANSYS resolving finned interface

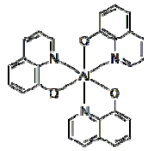
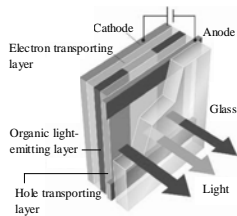


Mesh in micropolar model simulation resolving macroscale

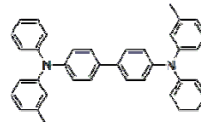
## Stress distribution along the interface centerline



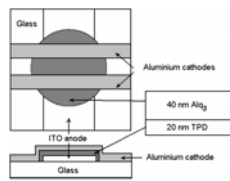
## OLED Encapsulation by Nano Anisotropic Conductive Adhesive With controlled filler Size and Properties



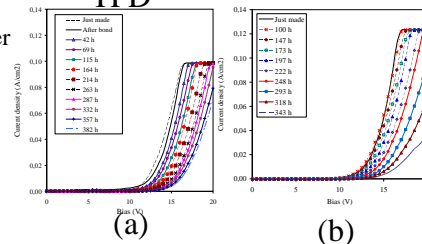
Alq3 as green light emitter



TPD



Operating OLED sample



(a) (b)

IV characteristics of OLED samples at different exposure time: (a) Encapsulated sample; (b) Reference sample.

## Acknowledgements

The presenter would like to acknowledge his co-workers and collaborators for the work and the financial support provided by the EU project Nanopack project and EU project: EC-GEPPO, by the SMIT Center member companies: Avantec, France, Flextronics, Heller Industries, USA, Note, Mydata Automation and Foab Elektronik, Sweden and Hitachi Chemicals, Japan, by the Chinese Ministry of Science and Technology (863 Program) on Nano Solder Paste with the contract no:2006AA03Z339 as well as by Intel, USA through its High Education Program with the contract No CNDA# 4126007.